



Wang
9/17/01

#13/Amdt E
A. Hou
10/2/01

Attorney Docket No.: 42390P7832

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:

Li-Shun Wang, John Chu

Serial No.: 09/476,633

Filed: December 31, 1999

For: **REMOVAL OF RESIDUE FROM A
SUBSTRATE**

Art Unit: 2823

Examiner: Garcia, J.

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TECHNOLOGY CENTER 2300

AMENDMENT AND RESPONSE TO OFFICE ACTION

BOX FEE AMENDMENT
Assistant Commissioner for Patents
Washington, D.C. 20231

Sir/Madam:

In response to the Office Action mailed on June 20, 2001, Applicants respectfully request entry of the amendment set forth below and consideration of the remarks which follow.

IN THE CLAIMS

Applicants respectfully request entry of the following new claims:

23. (New) A method of removing a particle from a surface of a metal plug formed in a via comprising:

introducing a first agent to a metal layer;

polishing the metal layer with the first agent; and

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01 FC:103 480.00 0P
02 FC:102

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